



Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		Complete if Known			
		Application Number	09/197,534		
		Filing Date	November 23, 1998		
		First Named Inventor	Shunpei YAMAZAKI et al.		
		Art Unit	2823		
		Examiner Name	William D. Coleman		
Sheet	1	of	1	Attorney Docket Number	740756-1894

U.S. PATENT DOCUMENTS					
Examiner Initials ¹	Cite No. ¹	U.S. Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
		US-			
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FOREIGN PATENT DOCUMENTS						
Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁴
		Country Code ³ Number ⁴ Kind Code ⁵ (if known)				
		JP 2-187294	07/23/1990	KAJIKAWA		AB

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		Itoga et al. "Laser Re-Crystallization Utilizing Beam Homogenizing Optical System" Japan Society of Applied Physics, Proceedings of 48 th Annual Meetings, 2 nd Part, 18 p-6-N-6, P. 537 (1987)	

Examiner Signature		Date Considered	3/19/04
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¹ Applicant's unique citation designation number (optional). ² See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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Submitted with USPTO Form 15, 2000

Sheet 1 of 4

Form PTO-1449 (Rev. 8-83)		U.S. Department of Commerce Patent and Trademark Office		Atty.Docket No. 0756-1894		Serial No. 09/197,534	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				Applicant Shunpei Yamazaki et al.			
				Filing Date November 23, 1998		Group 2874	
U.S. PATENT DOCUMENTS							
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		4,475,027	10/02/84	Pressley			
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		176715	03/89	Japan			Abst.
		220681	01/24/90	Japan			Abst.
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
	Pennington, K.S. et al., "CCD Imaging Array Combining Fly's Eye Lens with TDI for Increasing Light-gathering Ability", IBM Technical Disclosure Bulletin, Vol. 21, No.2, July 1978, pp. 857-858.						
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	"Enlargement of Poly-Si Film Grain Size by Excimer Laser Annealing and its Application to High-Performance Poly-Si Thin Film Transistor", Hiroyuki Kuriyama et al., Jpn. J. App. Phys., Vol. 30, No. 12B, December, 1991, pp. 3700-3703.						
	"Formation of p-n Junctions and Silicides in Silicon Using a High Performance Laser Beam Homogenization System", M. Wagner et al., Applied Surface Science 43 (1989), pp. 260-263.						
Examiner				Date Considered 3/19/04			
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See 257/335

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(Rev. 8-83)

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INFORMATION DISCLOSURE STATEMENT

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Applicant
Shunpei Yamazaki et al.

Filing Date
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Group
2874

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						Yes	No
	1239837	12/18/89	Japan			Abst.	
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	"Lateral Grain Growth of Poly-Si Films with a Specific Orientation by an Excimer Laser Annealing Method", Hiroyuki Kuriyama et al., Jpn. J. Appl. Phys. Vol. 32 (1993), Pt. 1, No. 128, pp. 6190-6195.
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						Yes	No
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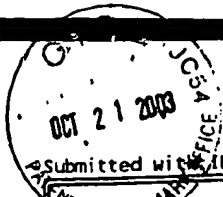
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Submitted with IDS on June 15, 2000

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U.S. PATENT & TRADEMARK OFFICE 1449
(Rev. 8-83)

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Patent and Trademark Office

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Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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		Filing Date: November 23, 1998		Group: 2874	

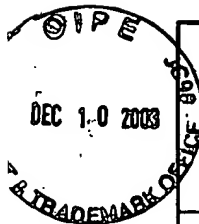
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Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)	
[Signature]	6,149,988	11/21/00	Shinohara et al.				

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Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	

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Examiner [Signature]	Date Considered 3/19/04
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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials ¹	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²

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